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利用形態 :機器利用、技術補助

利用課題名(日本語) :PECVD-DLC 傾斜多層膜を被覆した Si 微小構造体の引張強度特性

Program Title(English) : Tensile behaviors of micron-scaled silicon structure fully coated with bias-graded

DLC muilti-layer deposited by PECVD

利用者名(日本語) :夏園林、平井 義和

Username(English) :Y. Xia, <u>Y. Hirai</u>

所属名(日本語) :京都大学大学院工学研究科

Affiliation(English) : Graduate School of Eng., Kyoto Univ.

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#### 1. 概要(Summary)

DLC (Diamond Like Carbon) film is one of the promising coating material in MEMS industry deal to its many desirable properties. The biasgraded deposition by changing bias voltage stepwisely is an effective solution to release the internal stress. The modification of the interface regions between the substrate and the graded layers ensures a good adhesion. In this research, The tensile testing was carried on a micro-scaled Si structure which was fully coated by DLC film with different bias-graded types by PECVD method.

#### 2. 実験(Experimental)

## 【利用した主な装置】

[A2] I-line Stepper

[A54] Double-side mask aligner

[B8] Deep Reactive Ion Etching machine

[C22] Nano-indentation machine

## 【実験方法】

Tensile specimens were fabricated using SOI wafer. Upper and lower side photolithography were carried out by stepper and double-side mask aligner while the deep RIE machine was used for silicon trench etching from the both sides (Fig. 1). PECVD was used for the full-coated gradient DLC film at the fabricated specimens. The fracture toughness was measured by nano-indentataion method.

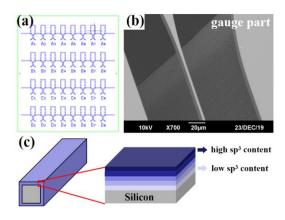


Fig.1 Sample fabrication

# 3. 結果と考察(Results and Discussion)

A summary of average tensile strengths is shown in Figure 2. Compared with single layer, coating parameter with 200/400/600 showed a much higher strength.

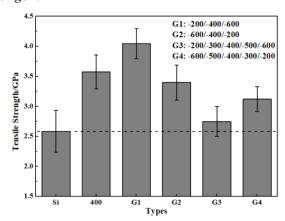


Fig.2 Average tensile strength

4. その他・特記事項(Others) なし

5. 論文・学会発表 (Publication/Presentation) なし

6. 関連特許(Patent) なし